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# VERIFICATION OF MAGNETIC FIELDS CALCULATION DATA IN THE MAGNETRON SPRAYING SYSTEM

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## Abstract

The purpose of this study was to compare the results of direct bench measurements of the topology and the magnitude of the magnetic field in the magnetron spraying system on permanent magnets with a 50 mm diameter target with the results of modeling obtained by the program of finite element analysis. Findings of the research show that the results of the measurements and calculations are in good agreement.

## Keywords

Magnetron spraying system, ion sputtering, magnetron, thin film coatings, numerical methods for modeling the magnetic field, magnetic field topology, magnetic field configuration optimization

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